Declaration of Vacuum Pump Contamination

Pumps International, Inc.

1045 American Pacific Drive.

Suite 100

Henderson NV 89074 Contact: Betsy Stanton Phone: 702-565-9384

Email Address: Bbrogan@garlic.com Website: http://www.pumpsint.com

ADDRESS ALL SHIPMENTS-ATTN: BETSY STANTON

Complete this form before sending any pumps to Pumps International, Inc. (PI) for repair. Fax and or email the completed form to PI and include a copy with each unit

Company:		Date:			
Contact:	Phone#:	Date: Email:			
Address:					
City:	State:	Zin:			
Manufacturer	Model				
PO#:	N:	:			
Reason for pump being	returned, please be spe	cific:			
If Turbo, cooled by: Ai	r Water				
If applicable check oil t	ype to return in unit:	PFPEHydrocarbon			
WARNING: Always us	se the proper safety pre	cautions when handling contaminated			
		ls of damaging & dangerous contaminants, but			
does not eliminate the h					
		istance if you have any questions.			
· · · · · · · · · · · · · · · · · · ·	-	nistry: (Please respond to each item!)			
Air (if no chemistry, che		Nitrogen (N2)			
Am (ii no chemistry, che Ammonia (NH3)	er here)	Nitrogen Triflouride (NF3)			
Argon (Ar)		Nitrous Oxide (N2O)			
Arsenic (As		Oxygen (O2)			
Arsine (AsH3)		Ozone (O3)			
Boron Trichloride (BCl.	3)	Phosphine (PH3)			
Boron Trifluoride (BF3)		Silane (SlH4)			
Carbon Tetrachloride (C		Sulfur Hexaflouride (SF6)			
Carbon Tetrafluoride (C	CF4)	Tetraethylorthosilicate (C2H2o4Si) (TEOS)			
Chlorine (Cl2)		Tetrafluoromethane (CF4) (Freon 14)			
Dichlorosilane (SlH2Cl2		Trifluoromethane (CHF3) (Freon 23)			
Hexafluoroethane (C2Fe		Trimethylboron (B (CH3)3)			
Hydrogen Bromide (HB	r)	Trimethylphosphite (C3HSO3P) (TMP)			
Hydrochloric Acid (HC		Tungsten Hexaflouride (WF6)			
Hydroflouric Acid (HF)					
Write in Chemicals if not lis	ted: (Chemicals not listed sh	hould include CAS #)			
*Attach MSDS sheets, if ava	ailable, to pump				

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Declaration of Vacuum Pump Contamination (cont.)

Unit has been exposed	to the following:	(Please res	pond to all that apply	!)
Non-hazardous Flar				•
Biological hazard T				
Radioactive Explos				
Carcinogenic Corro				
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T	. D //D .	T 6 4		
For Semiconductor on				
Implantation:	Deposition:	PVD:	TEOS-CVD:	_MCVD:
Etch:Polysilicone	: Metal:	Deep:	Trench: Silicide:	Oxide:
Additional Comments:				
F 111 G				
End User Signature:			Date:	